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APPLICATION NO. FILING DATE		FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/827,305	04/20/2004	Noriyuki Ito	112869.01	2565
25944 7	590 01/23/2006		EXAMINER	
OLIFF & BE	RRIDGE, PLC	NGUYEN, TAI V		
P.O. BOX 19928 ALEXANDRIA, VA 22320			ART UNIT	PAPER NUMBER
			3729	

DATE MAILED: 01/23/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

		Applica	tion No.	Applicant(s)				
Office Action Summary		10/827,	305	ITO ET AL.				
		Examin	er	Art Unit				
		Tai Van	Nguyen	3729				
	The MAILING DATE of this communi	cation appears on t	he cover sheet with the c	orrespondence ad	ddress -			
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.  - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.  - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).								
Status								
2a) ☐ 3) ☐ Dispositi	Since this application is in condition to closed in accordance with the practice on of Claims	b)⊠ This action is for allowance excepte the control of the contr	ot for formal matters, pro		e merits is			
5)□ 6)⊠ 7)⊠ 8)□	<ul> <li>4) Claim(s) <u>5-9</u> is/are pending in the application.</li> <li>4a) Of the above claim(s) is/are withdrawn from consideration.</li> <li>5) Claim(s) is/are allowed.</li> <li>6) Claim(s) <u>5-8</u> is/are rejected.</li> <li>7) Claim(s) <u>9</u> is/are objected to.</li> <li>8) Claim(s) are subject to restriction and/or election requirement.</li> </ul>							
Applicati	on Papers							
<ul> <li>9) The specification is objected to by the Examiner.</li> <li>10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.  Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).</li> <li>11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.</li> </ul>								
Priority u	ınder 35 U.S.C. § 119							
<ul> <li>12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).</li> <li>a) All b) Some * c) None of:</li> <li>1. Certified copies of the priority documents have been received.</li> <li>2. Certified copies of the priority documents have been received in Application No. 10/153,689.</li> <li>3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).</li> <li>* See the attached detailed Office action for a list of the certified copies not received.</li> </ul>								
2) Notic 3) Infor	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (P nation Disclosure Statement(s) (PTO-1449 or r No(s)/Mail Date <u>4/20/04</u> .		4) Interview Summary Paper No(s)/Mail Do 5) Notice of Informal F 6) Other:		O-152)			

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#### **DETAILED ACTION**

# Specification

1. The title of the invention is not descriptive. A new title is required that is clearly indicative of the invention to which the claims are directed.

2. The following title is suggested: A METHOD FOR FABRICATING A THIN FILM MAGNETIC HEAD.

# Claim Objections

3. Claim 5 objected to because of the following informalities:

In claim 5: The word "gas" (line 23) needs to be changed to -- gap --.

Appropriate correction is required.

## Claim Rejections - 35 USC § 102

4. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 5. Claims 5-7 are rejected under 35 U.S.C. 102(b) as being anticipated by Watanabe et al (US 6,157,526).

As applied to claim 5, Watanabe et al disclose a method for fabricating a thin film magnetic head including a magnetoresistive effective type thin film magnetic head element comprising a first and a second magnetic shielding films which are made of

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magnetic material, a first and a second shielding gap films which are made of non-magnetic material and located between the first and the second magnetic shielding films, a maretoresistive effective element film which is located between the first and the second shielding gap films, a first and a second longitudinal bias-applying films which are located in both sides of the magnetoresistive effective element film, and a first and a second electrode films which are located so as to cover edge portions of the magnetoresistive effective element film beyond the first and the second longitudinal bias-applying films, comprising the steps of:

forming the first shielding film (111, Fig. 4) on a given substrate (10), forming the first shielding gap film (121) on the first shielding film,

forming a maretoresistive (15) effective film on the first shielding gap film, partially etching and removing the maretoresistive effective film via a first mask fabricated thereon to pattern and form said magnetoresistive effective element film, forming the first and the second longitudinal bias-applying films (24) via said first mask at both sides of the maretoresistive effective element film so that the difference in surface level between the magnetoresistive effective element film and the first and second longitudinal bias-applying film is set within + 20nm (see Embodiment 2),

forming the first and the second electrode films (17) so as to cover edge portions of the magnetoresistive effective element film and the first and the second longitudinal bias- applying films, forming the second shielding gap (122) so as to cover the maretoresistive effective element film, the first and said second electrode films, and forming the second shielding film (112) on the second shielding gap film.

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As applied to claim 8, Watanabe et al disclose the first and the second longitudinal bias-applying films and said first and said second electrode films are formed by means of sputtering (see Embodiment 1).

#### Allowable Subject Matter

6. Claim 9 is objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

### Conclusion

- 7. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.
- 8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Tai Van Nguyen whose telephone number is 571-272-4567. The examiner can normally be reached on M-F (7:30 A.M 4:30 P.M).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Peter Vo can be reached on 571-272-4690. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

TN. January 09, 2006

> A. DEXTER TUGBANG PRIMARY EXAMINER